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Supporting Information

Na₃V₂(PO₄)₃-Supported Electrospun Carbon Nanofiber Nonwoven Fabric as Self-Standing Na-Ion Cell Cathode

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SUPPLEMENTARY MATERIAL

Na₃V₂(PO₄)₃-supported Electrospun Carbon Nanofiber Nonwoven Fabric as Self-Standing Na-ion Cell Cathode

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Conductivity measurements

The conductivity of CNF through and along the mat plane (σ_t ; σ_l , transversal and longitudinal, respectively) was evaluated. Two probes measurement was used to measure transversal and longitudinal resistance (R_t ; R_l). A schematic of the two setups used and relevant quantities are shown below. Mat thickness (t) was measured from SEM image and was 70 µm. CNF were punched in 10 mm disks. Contacts to the CNF were made with copper tape (resistance < 0.01 Ω) mounted on glass slide. A second glass slide was used to apply uniform pressure on top of the CNF. Current was swept from –1 to 1 mA with a step of 10 mA (Keithley 2400 SourceMeter; Keithley 2000 Multimeter for voltage measurement). Data were acquired with a LabView software already available in the laboratory. Transversal and longitudinal resistance were extracted from the linear fit of V versus I and σ_t , σ_l , computed as:

$$\sigma_t = \frac{t}{R_t h_t l_t} \quad \sigma_l = \frac{l_l}{R_l h_l t}$$



Scheme 1: Setup for the measurement of transversal and longitudinal resistance of CNF samples. Quantities reported were used to evaluate σ_t ; σ_l



Figure SI-1: a) PAN mat produced by electrospinning and the cut. b) Bended PAN mat showing high flexibility. c) SEM image of mat surface, showing PAN fibers randomly oriented, arranged in a non-woven structure.



Figure SI-2: a) Dependence of mat thickness on volume of spun solution for stabilized and carbonized fibers, b) example of SEM image used to measure the thickness of a stabilized sample.



Figure SI-3-SEM cross sections of stabilized mat spun with 200 and 2000 µL. No major morphological differences are visible along the mat section.



Figure SI-4: Effect of incomplete stabilization on CNF morphology. Green insets highlight melted PAN background.



Figure SI-5- Diffractogram of the annealed NVP (800 °C, 8 hrs) with the bars of reflection of the rhombohedral structure.



Figure SI-6 – Fitting of EIS spectra by using the equivalent circuit specified in the article.



Figure SI-7- Post-mortem SEM of the CNF/NVP electrode. The SEI can be appreciated as occlusion of the pores.



Figure SI-8- SEM (secondary electrons) image of the CNF/NVP electrode produced by Buchner filtration. The thickness (50 µm) is reported.



Figure SI-9 – XRD pattern of the CNF/NVP sample obtained by Buchner filtration treated at 800 $^{\circ}$ C for 2 hours.